

# United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/618,478	07/11/2003	Marvin S. Keshner	200308866-1	5298
22879	7590 06/05/2006		EXAMINER	
	HEWLETT PACKARD COMPANY CHEN, BRET P			BRET P
	2400, 3404 E. HARMONY R UAL PROPERTY ADMINI		ART UNIT	PAPER NUMBER
	INS, CO 80527-2400		1762	
			DATE MAILED: 06/05/2006	4

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
Office Antique Company	10/618,478	KESHNER ET AL.				
Office Action Summary	Examiner	Art Unit				
	B. Chen	1762				
The MAILING DATE of this communicatio Period for Reply	n appears on the cover sheet	with the correspondence address				
A SHORTENED STATUTORY PERIOD FOR R WHICHEVER IS LONGER, FROM THE MAILIN  - Extensions of time may be available under the provisions of 37 C after SIX (6) MONTHS from the mailing date of this communicati  - If NO period for reply is specified above, the maximum statutory  - Failure to reply within the set or extended period for reply will, by Any reply received by the Office later than three months after the earned patent term adjustment. See 37 CFR 1.704(b).	NG DATE OF THIS COMMUN CFR 1.136(a). In no event, however, may on. period will apply and will expire SIX (6) More statute, cause the application to become	NICATION. a reply be timely filed  ONTHS from the mailing date of this communication ABANDONED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on	1)⊠ Responsive to communication(s) filed on 12 April 2006.					
2a) This action is <b>FINAL</b> . 2b) ⊠	This action is <b>FINAL</b> . 2b)⊠ This action is non-final.					
3) Since this application is in condition for al	lowance except for formal ma	atters, prosecution as to the merits i	is			
closed in accordance with the practice un	ider <i>Ex parte Quayle</i> , 1935 C	.D. 11, 453 O.G. 213.				
Disposition of Claims						
4)  Claim(s) 1-14 is/are pending in the applic 4a) Of the above claim(s) 1-7 is/are withdr 5)  Claim(s) is/are allowed. 6)  Claim(s) 8-14 is/are rejected. 7)  Claim(s) is/are objected to. 8)  Claim(s) are subject to restriction a	rawn from consideration.					
Application Papers						
9) ☐ The specification is objected to by the Exa  10) ☑ The drawing(s) filed on 11 July 2003 is/are  Applicant may not request that any objection to Replacement drawing sheet(s) including the control of the oath or declaration is objected to by the	e: a)⊠ accepted or b)⊡ objo to the drawing(s) be held in abey correction is required if the drawir	rance. See 37 CFR 1.85(a). ng(s) is objected to. See 37 CFR 1.121(	(d).			
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for fo a) All b) Some * c) None of:  1. Certified copies of the priority docu 2. Certified copies of the priority docu 3. Copies of the certified copies of the application from the International B * See the attached detailed Office action for	ments have been received. ments have been received in e priority documents have bee sureau (PCT Rule 17.2(a)).	Application No en received in this National Stage				
Attachment(s)						
<ol> <li>Notice of References Cited (PTO-892)</li> <li>Notice of Draftsperson's Patent Drawing Review (PTO-943)</li> <li>Information Disclosure Statement(s) (PTO-1449 or PTO/S Paper No(s)/Mail Date</li> </ol>	l8) Paper N	v Summary (PTO-413) o(s)/Mail Date f Informal Patent Application (PTO-152) 				

Application/Control Number: 10/618,478 Page 2

Art Unit: 1762

#### **DETAILED ACTION**

Claims 1-14 are pending in this application.

#### Election/Restrictions

Applicant's election of claims 8-14 in the reply filed on 4/12/06 is acknowledged. Because applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)).

## Specification

Applicant is reminded of the proper content of an abstract of the disclosure.

A patent abstract is a concise statement of the technical disclosure of the patent and should include that which is new in the art to which the invention pertains. If the patent is of a basic nature, the entire technical disclosure may be new in the art, and the abstract should be directed to the entire disclosure. If the patent is in the nature of an improvement in an old apparatus, process, product, or composition, the abstract should include the technical disclosure of the improvement. In certain patents, particularly those for compounds and compositions, wherein the process for making and/or the use thereof are not obvious, the abstract should set forth a process for making and/or use thereof. If the new technical disclosure involves modifications or alternatives, the abstract should mention by way of example the preferred modification or alternative.

The abstract should not refer to purported merits or speculative applications of the invention and should not compare the invention with the prior art.

Where applicable, the abstract should include the following:

- (1) if a machine or apparatus, its organization and operation;
- (2) if an article, its method of making;
- (3) if a chemical compound, its identity and use;
- (4) if a mixture, its ingredients;
- (5) if a process, the steps.

Extensive mechanical and design details of apparatus should not be given.

It is noted that the claimed invention is directed to a method. The examiner suggests amending the abstract to reflect same.

The title of the invention is not descriptive. A new title is required that is clearly indicative of the invention to which the claims are directed.

It is noted that the claimed invention is directed solely to a method. The examiner suggests amending the title to reflect same.

#### Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 8-14 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

In claim 8 line 11, the term "intrinsic silicon layers" is deemed vague and indefinite. It is not clear what "intrinsic" means. Clarification is requested.

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Art Unit: 1762

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Claims 8-14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Won et al. (20030143410A1) or Shimuzu (5,824,345) when either is taken in view of Dickson et al. (4,690,830). Won discloses a method for reducing contamination in the deposition of an amorphous silicon film by CVD (abstract) in which the deposition gas mixture is hydrogen and silane (paragraph 11). The reactor can be a radio-frequency plasma enchanced chemical vapor deposition reactor (paragraph 27) and there is no recitation that dopants are introduced. The substrate is placed on a susceptor 216 within vacuum chamber 213 which is surrounded by a reactor housing 212 (paragraph 27).

Shimuzu discloses a method of fabricating a field effect thin film transistor in which a first amorphous semiconductor layer is deposited on a gate insulating film and transformed to a micro-crystal semiconductor layer by exposing it to hydrogen plasma produced by hydrogen discharge (col.2 lines 48-64). Specifically, an amorphous silicon film about 15 nm thick which is to be transformed into a micro-crystal silicon film is deposited by plasma CVD in a plasma CVD chamber filled with a mixture gas of silane gas and hydrogen gas as a reaction gas under conditions of reaction gas pressure of 120 Pa, temperature of the glass substrate 1 at the film formation of 250.degree. C. and RF power density at 13.56 MHz of 0.04 W/cm.sup.2 (col.4 lines 28-34).

However, both Won and Shimuzu fail to teach recirculating silane. Dickson discloses a method of forming hydrogenated amorphous silicon alloy films in a deposition chamber (col.1 lines 31-49) by introducing into a deposition chamber during deposition a deposition gas mixture (col.2 lines 55-66). The gas mixture can contain silane (col.5 lines 38-41 and col.9 lines 50-60) and can be recirculated (col.13 lines 3-25). It would have been obvious to recirculate the silane in Won or Shimuzu's process with the expectation of being environmentally friendly as recycling gaseous materials is well known to conserve on the amount of actual material being utilized.

The limitations of claims 9-14 have been addressed above.

Harshbarger et al. (6,352,910) has been cited as relevant art.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to B. Chen whose telephone number is (571) 272-1417. The examiner can normally be reached on 7:30am - 4:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Timothy Meeks can be reached on (571) 272-1423. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Bc 5/31/06

BRET CHEN
PRIMARY EXAMINER